line 5, before "formed" insert --is--;
line 7, after "substrate" delete "; and a"
and insert therefor --. A--;
line 7, before "filled" insert --is--;

Page 6, line 3, delete "ll" and insert therefor
--ll1--;

Page 7, line 1, delete "owing" and insert therefor
--due--;

IN THE CLAIMS:

- (Once Amended) A dynamic random access memory having a trench capacitor, said memory comprising:
  - a semiconductor substrate of one conduction type;
  - a trench formed in said semiconductor substrate;
- a first conductive layer formed on a deep portion [the]
  of an inner surface of said trench and not being formed in
  [except for] a region [adjacent] close to [the opening portion]
  an entrance of said trench;
- a dielectric layer <u>being</u> formed on said first conductive layer [exposed] in said trench and <u>being formed on said inner</u> [the] surface of <u>said trench in said region close to said entrance of said trench</u> [said semiconductor substrate];
- a second conductive layer [filled] <u>filling</u> in said trench through said dielectric layer;

said first conductive layer, said dielectric layer, and said second conductive layer constituting a storage capacitor; and